# Monthly LabAdviser update: 1/8 2014

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| Updated Subject | Contributor | Link to the updated pages |
| **III-V etches**  Several new etches rates added | **Luisa Ottaviano @photonics** | [/Wet\_III-V\_Etches](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Wet_III-V_Etches) |
| **LASER**   * Adding graph for Average output power for IPG 1064nm laser * Adding graph for Pulse energy regarding the repetition rate for the IPG 1064nm laser | **Chantal Silvestre @danchip** | [Laser\_Micromachining\_Tool](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Back-end_processing/Laser_Micromachining_Tool)  [d140618\_AverageOutputPower\_IPG.jpg](http://labadviser.danchip.dtu.dk/images/7/7d/140618_AverageOutputPower_IPG.jpg)  [PulseEnergy](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Back-end_processing/Laser_Micromachining_Tool/PulseEnergy) |
| **E-beam**   * Espacer – prevent charging of nn-conductiong substrates * CSAR: new positive e-beam resist | **Tine Greibe @danchip** | [Espacer](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Espacer)  [CSAR](http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/CSAR) |
| **New equipment in pipe line**  Update | **Danchip** | [New\_equipment\_in\_the\_pipeline\_and\_Old\_equipment\_for\_decommissioning](http://labadviser.danchip.dtu.dk/index.php/LabAdviser/New_equipment_in_the_pipeline_and_Old_equipment_for_decommissioning) |